

(19) World Intellectual Property  
Organization  
International Bureau



(43) International Publication Date  
14 July 2005 (14.07.2005)

PCT

(10) International Publication Number  
**WO 2005/064679 A1**

(51) International Patent Classification<sup>7</sup>: **H01L 23/544**,  
G03F 7/20

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(21) International Application Number:  
PCT/IB2004/052724

(81) Designated States (*unless otherwise indicated, for every  
kind of national protection available*): AE, AG, AL, AM,  
AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN,  
CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI,  
GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE,  
KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD,  
MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG,  
PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM,  
TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM,  
ZW.

(22) International Filing Date: 9 December 2004 (09.12.2004)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:  
03104956.2 23 December 2003 (23.12.2003) EP

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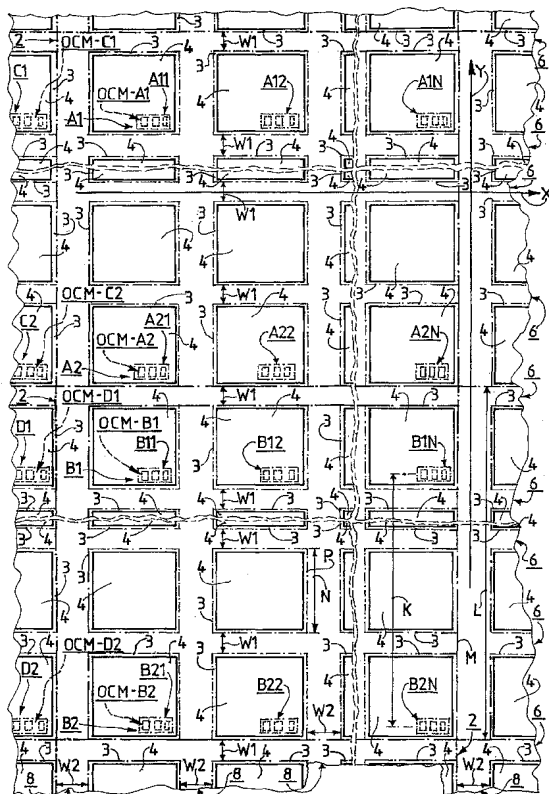
(84) Designated States (*unless otherwise indicated, for every  
kind of regional protection available*): ARIPO (BW, GH,  
GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM,  
ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM),  
European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI,

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[Continued on next page]

(54) Title: WAFER WITH OPTICAL CONTROL MODULES IN IC FIELDS



(57) Abstract: In a wafer (1) with a number of exposure  
fields (2), each of which exposure fields comprises a  
number of lattice fields (3) with an IC (4) located therein,  
two groups (5, 7) of saw paths (6, 8) are provided and two  
control module fields (A1, A2, B1, B2, C1, C2, D1, D2)  
are assigned to each exposure field, each of which control  
module fields contains at least one optical control module  
(OCM-A1, OCM-A2, OCM-B1, OCM-B2, OCM-C1,  
OCM-C2, OCM-D1, OCM-D2) and lies within the exposure  
field in question and comprises a plurality of control  
module field sections (A11, A12, ..., A1N and A21,  
A22, ..., A2N and B11, B12, ..., B1N and B21,  
B22, ..., B2N and C11 and C21 and D11 and D21)  
and is distributed among several lattice grids (3),  
wherein each control module field section (A11 to D2N)  
is located in a lattice field and contains at least one control  
module component (10, 11, 12, 13, 14, 15, 16, 17, 18).



FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO,  
SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN,  
GQ, GW, ML, MR, NE, SN, TD, TG).

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**Published:**

— *with international search report*